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## PATENT ABSTRACTS OF JAPAN

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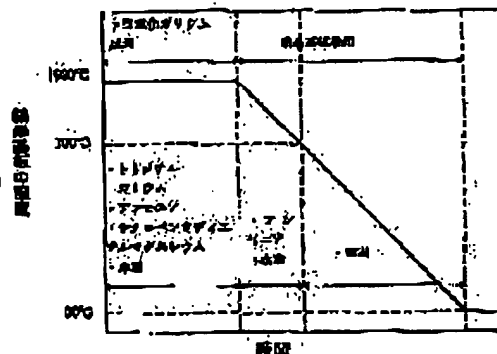
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## (54) VAPOR GROWTH METHOD OF LOW-RESISTANCE P-TYPE GALLIUM NITRIDE-BASED COMPOUND SEMICONDUCTOR

## (57)Abstract:

**PROBLEM TO BE SOLVED:** To provide a p-type gallium nitride-based compound with high crystal quality and low resistance without using an additional step in a vapor growth method suitable for mass product, by cooling a substrate crystal at a given temperature in atmosphere of carrier gas excluding hydrogen just after the crystal is grown in the vapor growth step.

**SOLUTION:** A crystal substrate including p-type gallium nitride has a temperature of 1030° C at a crystal growth step. When the crystal substrate is cooled after crystal growth, the vapor phase atmosphere is made of hydrogen carrier gas and ammonia at a temperature of 700° C or above, and at the temperature of 700° C the gas is changed to only nitrogen gas. The crystal surface is subjected to heat deterioration when the substrate is cooled at 700° C or below, and after the crystal is cooled, the gallium nitride-based compound semiconductor layer is etched and removed. Since the atmosphere includes only nitrogen when the substrate crystal is cooled at 700° C or below, hydrogen gas is prevented from diffusing out of the crystal surface. After the cooling of the crystal, a desired structure is obtained only by etching the deteriorated crystal surface.



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